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Publication number: **0 422 628 A3**

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EUROPEAN PATENT APPLICATION

21 Application number: 90119460.5

51 Int. Cl.⁵: G03F 7/039, G03F 3/10

22 Date of filing: 11.10.90

30 Priority: 13.10.89 US 421546

43 Date of publication of application:
17.04.91 Bulletin 91/16

64 Designated Contracting States:
DE FR GB IT

66 Date of deferred publication of the search report:
26.02.92 Bulletin 92/09

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54 Photosensitive element.

57 A photosensitive element is provided wherein the photosensitive composition contains a polymeric compound having acid-degradable crosslinkages and a component that generates acid upon exposure to actinic radiation.

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EUROPEAN SEARCH REPORT

Application Number

EP 90 11 9460

DOCUMENTS CONSIDERED TO BE RELEVANT			
Category	Citation of document with indication, where appropriate, of relevant passages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int. Cl.5)
A	PATENT ABSTRACTS OF JAPAN vol. 9, no. 197 (E-335)(1920) 14 August 1985 & JP-A-60 064 432 (FUJITSU K.K.) 13 April 1985 *abstract ** ---	1,17	G 03 F 7/039 G 03 F 3/10
A	FR-A-2 290 458 (THOMSON CSF) *the whole document ** ---	1,17	
A	FR-A-2 305 757 (HOECHST AG) *the whole document ** ---	1,17	
A	JOURNAL OF IMAGING TECHNOLOGY. vol. 11, no. 4, August 1985, SPRINGFIELD US pages 146 - 157; PAPPAS S.P.: 'Photogeneration of acid :A review of basic principles for resist imaging applications' *the whole document ** ---	1	
D,A	US-A-4 663 269 (NARANG S.C., ATTARWALA S.) *the whole document ** ---	1,17	
The present search report has been drawn up for all claims			TECHNICAL FIELDS SEARCHED (Int. Cl.5)
			G 03 F
Place of search		Date of completion of search	
The Hague		19 December 91	
		Examiner	
		LUDI M.M.B.	
<div style="display: flex; justify-content: space-between;"> <div> <p style="margin: 0;">CATEGORY OF CITED DOCUMENTS</p> <p style="margin: 0;">X: particularly relevant if taken alone</p> <p style="margin: 0;">Y: particularly relevant if combined with another document of the same category</p> <p style="margin: 0;">A: technological background</p> <p style="margin: 0;">O: non-written disclosure</p> <p style="margin: 0;">P: intermediate document</p> <p style="margin: 0;">T: theory or principle underlying the invention</p> </div> <div> <p style="margin: 0;">E: earlier patent document, but published on, or after the filing date</p> <p style="margin: 0;">D: document cited in the application</p> <p style="margin: 0;">L: document cited for other reasons</p> <p style="margin: 0;">&: member of the same patent family, corresponding document</p> </div> </div>			